

APPARATUS AND METHOD FOR LARGE AREA CHEMICAL VAPOR DEPOSITION USING MULTIPLE EXPANDING THERMAL PLASMA GENERATORS

Abstract of Disclosure

Chemical vapor deposition is performed using a plurality of expanding thermal plasma generating means to produce a coating on a substrate, such as a thermoplastic and especially a polycarbonate substrate. The substrate is preferably moved past the generating means. Included are methods which coat both sides of the substrate or which employ multiple sets of generating means, either in a single deposition chamber or in a plurality of chambers for deposition of successive coatings. The substrate surfaces spaced from the axes of the generating means are preferably heated to promote coating uniformity.

Figures

Figure 1: A line graph showing the relationship between the number of hours spent on a task and the number of errors made. The x-axis represents 'Hours' (0 to 10) and the y-axis represents 'Errors' (0 to 100). The data points are as follows:

Hours	Errors
1	10
2	20
3	30
4	40
5	50
6	60
7	70
8	80
9	90
10	100